

SUBSTRATE AND SUBSTRATE PROCESSING METHOD

ABSTRACT

A substrate includes a photoresist film and an organic film. The photoresist film includes a first metal oxide and reacts with extreme ultraviolet (EUV) light. The organic film is provided under the photoresist film, and includes a second metal oxide which has metal-oxygen binding energy lower than metal-oxygen binding energy of the first metal oxide constituting the photoresist film, and from which oxygen is dissociated by the EUV light.

(Fig. 4)